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Picosecond Ultrasonics with Miniaturized Semiconductor Lasers

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Abstract: There is a great desire to extend ultrasonic techniques to the imaging and characterization of nanoobjects. This can be achieved by picosecond ultrasonics, where by using ultrafast lasers it is possible to generate and detect acoustic waves with frequencies up to terahertz and wavelengths down to nanometers. In our work we present a picosecond ultrasonics setup based on miniaturized mode-locked semiconductor lasers, whose performance allows us to obtain the necessary power, pulse duration and repetition rate. Using such a laser, we measure the ultrasonic echo signal with picosecond resolution in a 112 nm thick Al film deposited on a semiconductor substrate. We show that the obtained signal is as good as the signal obtained with a standard bulky mode-locked Ti-Sa laser. The experiments pave the way for designing integrated portable picosecond ultrasonic setups on the basis of miniaturized semiconductor lasers.

Keywords: Picosecond ultrasonics
Semiconductor lasers
Coherent Phonons

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1. Introduction

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Picosecond ultrasonics (PU) is an advanced research field which aims to extend traditional acoustic techniques to the gigahertz (GHz) and terahertz (THz) frequency ranges [1,2]. It started in the late 1980ies with the development of ultrafast lasers and nowadays PU shows great potential for elastic nanoscopy [3] and ultrafast control of electronic and optical devices [4-6]. PU imaging with sub-nanometer depth resolution is used to study nanostructures [7,8] including biological objects [9-11], chemical reactions [12], adhesion of nanolayers [13,14] and profile inhomogeneity [15].

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The main element of a PU setup is a pico- or femtosecond laser which output is split in two beams used for pumping and probing the system of interest. In most of PU experiments the pump beam is focused onto a thin metal film which acts as an thermoelastic transducer. After being hit by the pump pulse, the film expands in a time of ~ 1 ps and, as a consequence, a coherent elastic wave packet with frequencies up to several hundreds of GHz is injected into the specimen or device. The critical parameters for PU is the energy density J in the focus spot of the laser pump pulse, the pulse duration Δt , which limits the temporal resolution and correspondingly the maximum frequency in the ultrasonic wave packet, and the laser repetition rate f , which determines the accumulation time. The values for J , Δt and f that can reliably be reached, cover a wide range ($J=10^{-6}$ - 10^{-2} J/cm², $\Delta t \leq 1$ ps and $f=10$ - 10^9 Hz) using different experimental schemes and can easily be achieved using commercial femtosecond lasers. However, all PU setups are mounted on optical tables and use bulky, not portable lasers which so far has limited the application potential of PU in geology, biology and medicine.

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Therefore, it is very attractive to develop a portable PU setup with the elements integrated on a single chip which would facilitate its flexible application to an object and perform PU in situ during a short exposure time. The main element of such a prospective device is the ultrafast pulsed laser providing pulses with a duration ≤ 1 ps and sufficiently high power, but most importantly this laser should have a compact size to be flexibly transportable. Only recently such miniaturized mode-locked lasers based on semiconductor strip devices reliably operational with parameters that are attractive for PU experiments were designed [16-18]. Therefore, the task to establish PU pump-probe experiments exploiting these compact lasers can be tackled.

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In the present paper we describe pump-probe PU experiments with mode-locked semiconductor strip lasers. As specimen for the PU studies we use an Al metal film, which is widely used as thermoelastic transducer in PU experiments [19], with a thickness of 112 nm. The measured pump-probe signals have similar signal to noise ratios as the signals obtained with a conventional PU setup based on commercial mode-locked titanium-sapphire laser. Finally, we discuss various possibilities for the development of a single chip based PU device on the basis of ASOPS technology [20] which does not require a bulky delay line in PU pump-probe experiments.

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2. Mode-Locked Laser Device

67 In the experiments we used a laser fabricated by a MOCVD-grown AlGaAs/GaAs epilayer
68 structure with an InGaAs-based active quantum-well (QW) region consisting of two 4.4 nm-thick
69 $\text{In}_{0.18}\text{Ga}_{0.82}\text{As}$ QWs separated by a 9 nm-thick $\text{Al}_{0.2}\text{Ga}_{0.8}\text{As}$ barrier. The parameters of the layers and the
70 layer sequence are presented in Table 1. The active region, designed to emit at a wavelength of around
71 930 nm, is sandwiched between two 120 nm graded-index AlGaAs layers and two $\text{Al}_{0.32}\text{Ga}_{0.68}\text{As}$
72 claddings to provide electron and optical confinement. The lower AlGaAs cladding contains a graded far-
73 field reduction layer that enlarges the mode size in the vertical direction, thus reducing both the vertical
74 beam divergence and the optical power density [16].

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76 **Table 1.** Epitaxial layer structure of the AlGaAs-based wafer.

Layer Type	Materials	THKNS μm	Dopant cm^{-3}
Top Cladding			Zinc
CAP layer	GaAs	0.1	$10^{19} \div 10^{20}$
Matching	$\text{Al}_{0.05}\text{Ga}_{0.95}\text{As}$	0.12	$10^{18} \div 5 \cdot 10^{18}$
p-cladding	$\text{Al}_{0.32}\text{Ga}_{0.68}\text{As}$	1.7	10^{18}
p-cladding	$\text{Al}_{0.32}\text{Ga}_{0.68}\text{As}$	0.2	$5 \cdot 10^{17} \div 10^{18}$
Active			none
Graded Index	$\text{Al}_{0.2}\text{Ga}_{0.8}\text{As}$ - $\text{Al}_{0.32}\text{Ga}_{0.68}\text{As}$	0.12	-
QW	$\text{In}_{0.12}\text{Ga}_{0.88}\text{As}$	0.0044	-
Barrier	$\text{Al}_{0.2}\text{Ga}_{0.8}\text{As}$	0.009	-
QW	$\text{In}_{0.12}\text{Ga}_{0.88}\text{As}$	0.0044	-
Graded Index	$\text{Al}_{0.27}\text{Ga}_{0.73}\text{As}$ - $\text{Al}_{0.2}\text{Ga}_{0.8}\text{As}$	0.07	-
Bottom			Silicon
n-cladding	$\text{Al}_{0.3}\text{Ga}_{0.7}\text{As}$ - $\text{Al}_{0.27}\text{Ga}_{0.73}\text{As}$	0.03	10^{17}
n-cladding	$\text{Al}_{0.32}\text{Ga}_{0.68}\text{As}$ - $\text{Al}_{0.27}\text{Ga}_{0.73}\text{As}$	0.02	$5 \cdot 10^{17} \div 10^{17}$
n-cladding	$\text{Al}_{0.32}\text{Ga}_{0.68}\text{As}$	0.75	$5 \cdot 10^{17}$
F.F.R layer	$\text{Al}_{0.29}\text{Ga}_{0.71}\text{As}$ - $\text{Al}_{0.32}\text{Ga}_{0.68}\text{As}$	0.35	$5 \cdot 10^{17}$
F.F.R layer	$\text{Al}_{0.32}\text{Ga}_{0.68}\text{As}$ - $\text{Al}_{0.29}\text{Ga}_{0.71}\text{As}$	0.35	$5 \cdot 10^{17}$
n-cladding	$\text{Al}_{0.32}\text{Ga}_{0.68}\text{As}$	1.6	$7 \cdot 10^{17}$
Matching	$\text{Al}_{0.05}\text{Ga}_{0.95}\text{As}$ - $\text{Al}_{0.32}\text{Ga}_{0.68}\text{As}$	0.2	$10^{18} \div 7 \cdot 10^{17}$
Substrate	GaAs	645	Silicon

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78 The cross section of the laser is shown in Fig.1(a). The optical waveguide is fabricated by optical
79 lithography and reactive ion etching with a SiCl_4 gas chemistry [21]. The waveguide has a width of 2.5
80 μm and an etching depth of approximately 2.1 μm to ensure single spatial mode operation. The total
81 cavity length of 2.6 mm provides a cavity round trip time of 62 ps, corresponding to a repetition rate of 16
82 GHz under mode-locking conditions. The typical power-current voltage characteristics for such type of
83 lasers is shown in Fig. 1(b). The passive mode-locking is achieved by introducing an intensity dependent
84 loss element into the laser cavity, i.e., a saturable absorber. The absorber consists of an additional
85 reversely biased section along the laser cavity [17]. Because of the saturation arising from the band filling
86 effect, pulses as short as 1 ps can be generated under appropriate biasing conditions [18].

87 In the PU experiments we used a bar which consists of 20 lasers with identical design and similar
 88 characteristics. An optical image of a fragment of the bar is shown in Fig. 1 (c). The size of the chip is
 89 $10 \times 2.5 \text{ mm}^2$ while the size of the individual strip is $0.5 \times 2.5 \text{ mm}^2$. The laser emission spectra for different
 90 absorber voltages measured at a bias current of 120 mA are shown in Fig.1 (d). It is seen that the emission
 91 shifts to shorter wavelengths and the spectrum broadens with increasing voltage. In the PU experiments
 92 we used 1.5 V on the absorber so that the laser emits at 928 nm.

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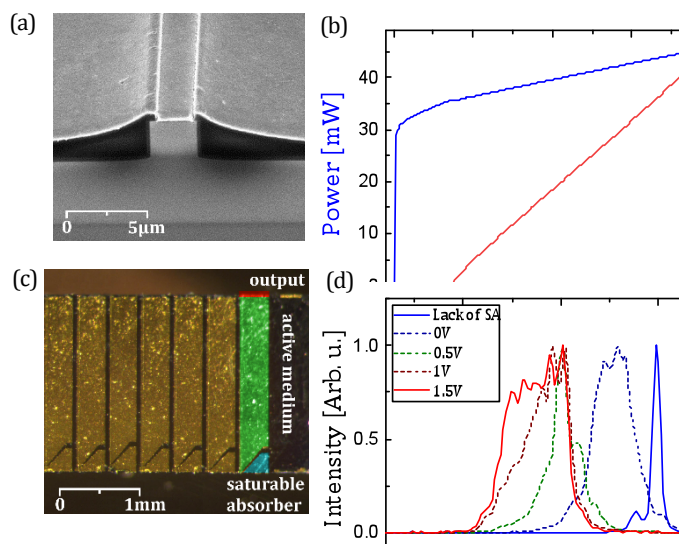


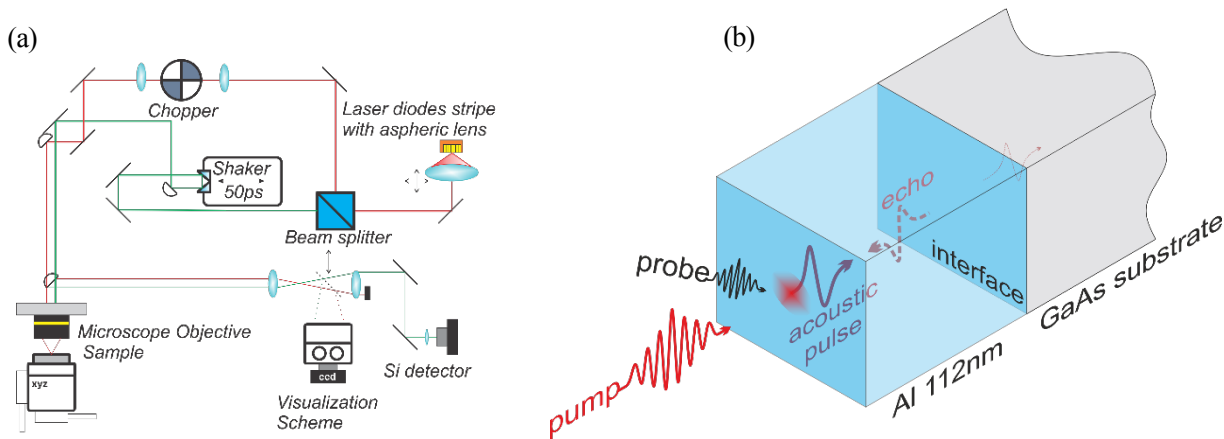
Fig. 1. Mode locked semiconductor laser: (a) cross section of the laser; (b) current voltage and output power characteristics of the laser with zero bias on the absorber; (c) optical image of the laser bars on the chip; (d) emission spectra of the laser for various biases applied to the absorber.

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3. Experiment

96 The schematic of the PU pump probe setup is shown in Fig.2 (a). The laser beam is collimated by the
 97 aspherical lens with focus distance of 3 mm. The beam is split into two paths for pump and probe. The
 98 pump passes the chopper for 10 kHz frequency modulation and the probe is sent to the shaker in order to
 99 achieve a variable time delay between the pulses in a range of up to 50 ps. Subsequently both beams go
 100 through the x15 reflective microscope objective and are focused to a spot with a diameter of $5 \mu\text{m}$ on the
 101 Al film as shown in Fig. 2(a). The average pump power used is 15 mW, which corresponds to $\sim 4 \mu\text{J}/\text{cm}^2$
 102 excitation density on the Al film. The beams are reflected from the sample, the pump is blocked and the
 103 probe beam is sent onto the silicon photodiode. A lock-in amplifier with the integration time of 3 ms is
 104 used. For precise overlap on the sample, an optimized visualization scheme with a microscope set-up was
 105 developed. The mirror controls allow one to adjust the pump and probe beam paths and to control
 106 precisely the position of the two spots on the sample. The total area of the setup is $80 \times 80 \text{ cm}^2$.



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108 **Fig. 2.** Experimental setup for picosecond ultrasonic experiments: (a) experimental schematic; (b) scheme
 109 demonstrating the generation and detection of the echo strain pulse in the Al film.

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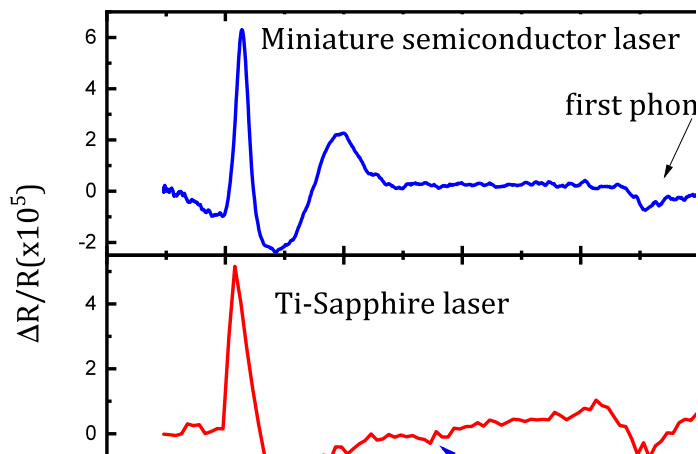
111 Figure 3(a) shows the measured PU signal recorded with the semiconductor laser described above. The
 112 pump pulse excites the Al film at $t=0$. The strong response observed in the time interval between $t=0$ and
 113 15 ps is typical for ultrafast pump-probe experiments [1,2,19] and is due to contributions from hot
 114 electrons, rapid lattice heating and generated stress. The existence of several contributions makes it
 115 difficult to extract the contribution from the generated stress and respective strain. The negative pulse
 116 with a maximum at $t=36$ ps corresponds to the first echo of the strain pulse reflected at the Al/GaAs
 117 interface as shown in the inset of Fig. 2(b). Indeed, the arrival time of the maximum is expected at $t_0=2d/s$
 118 $=35$ ps, where $d=112$ nm is the nominal thickness of the Al film and $s=6420$ m/s is the velocity of
 119 longitudinal sound in Al. The slight difference of 1ps between the expected and measured values of the
 120 echo arrival time is due to a slight difference between the actual and nominal thicknesses of the Al film.
 121 The reflection R of the acoustic wave at the Al/GaAs interface depends on the acoustic impedances $Z=\rho s$
 122 of the materials, where ρ is the density:

$$123 \quad R = \frac{Z_{GaAs} - Z_{Al}}{Z_{GaAs} + Z_{Al}} \quad (1)$$

124 Substituting the values for Z into Eq. (1) we get $R=0.2$ and the reflected strain pulse does not change the
 125 phase at the Al/GaAs interface. If there was no contribution from the hot electrons at time around $t=0$, we
 126 could expect a negative strain pulse with an amplitude 5 times larger than the amplitude of the echo
 127 signal. At $t=0$ the pump-probe signal is positive which means that the contribution from the hot electrons

Fig. 3. Picosecond ultrasonic signals: (a) measured with the mode-locked semiconductor laser with repetition rate 16 GHz; (b) measured with 80 MHz commercial Ti-sapphire laser.

128 is several times larger than the expected negative contribution from the thermo-elastic effect.



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130 The PU signal in Fig. 3(a) measured with the miniaturized semiconductor laser has a shape
131 similar to the PU signals obtained in earlier experiments with Al films [19]. To be sure that our results
132 obtained with the semiconductor laser are basically identical to those obtained with a conventional
133 femtosecond laser, we performed PU experiments on the same Al film with a Ti-sapphire laser with 82
134 MHz repetition rate at 900 nm wavelength and 150 fs pulse duration. However, the excitation energy
135 density in the pump pulse in this case is an order of magnitude higher, resulting in a stronger temperature
136 rise of the Al film. The measured pump-probe trace is shown in Fig. 3(b). We see that the echo signal has
137 a similar temporal shape and appears exactly at the same time as in the experiments with the miniaturized
138 semiconductor laser. The measurement times in both experiments were the same, around 5 minutes, and
139 the signal to noise ratios are almost the same. There is a difference in the temporal shapes around $t=0$
140 which is likely due to the 200-fold difference in repetition rates and the incomplete recovery of the Al
141 film to lattice temperature in the experiment with the semiconductor laser. In the experiments with Ti-
142 Sapphire laser there is a barely visible signal at $t=17-18$ ps marked by dashed arrow in Fig. 3. This
143 feature, explained by the electron diffusion along the Al film [19], is not observed in experiments with
144 semiconductor laser which likely due to much longer pulse duration and much higher repetitions rate
145 relatively to Ti-Sapphire oscillator.

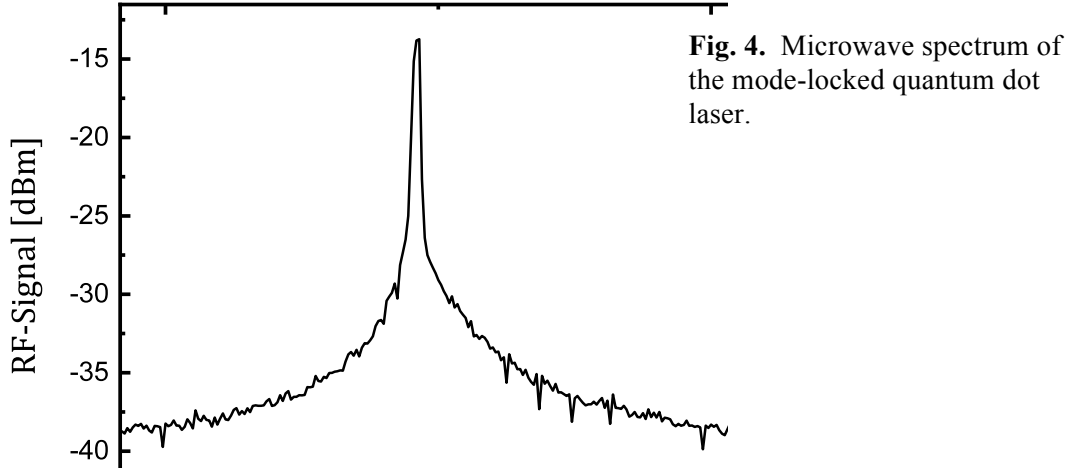
146 4. Discussion

147 Our experiments show that miniaturized mode-locked semiconductor lasers are very well suitable
148 for PU experiments. The typical property of these lasers is the high repetition rate which is given by the
149 length of the laser cavity and typically is in the range of tens of GHz. The high repetition rate has the
150 advantage of getting the required signal to noise ratio in a shorter time in comparison with conventional
151 mode-locked lasers with repetition rates ~ 100 MHz, using the same pump fluence in a single pulse.
152 However, the disadvantage of the high-repetition rate is that the system potentially has no time to recover
153 to the initial state. As we see in our experiments this does not have a significant effect on the echo signal,
154 but could become important when studying PU signals that last longer than hundreds of picoseconds. The

155 challenge of getting short laser pulses in miniaturized lasers with durations below a few ps may not be
156 met with every laser and requires careful selection, but our experiments show that a temporal resolution
157 of $\Delta t \approx 1$ ps can be achieved. The duration of the optical pulses which limits the temporal resolution of the
158 PU experiments limits also the highest frequency of the detected acoustic wave. With durations of ~ 1 ps
159 for the pump and probe pulses, acoustic frequencies of several hundreds of GHz are achievable. PU
160 experiments in this frequency range are high on demand in nondestructive material characterization and
161 imaging of biological objects, including live cells.

162 The miniaturized mode-locked semiconductor lasers for PU experiments may have even higher
163 average power than the one used so far: While this device relies on a standard two-segment ridge
164 waveguide utilizing quantum well gain, great promise is held by implementing quantum dots as active
165 gain material into the laser. Quantum dots offer several advantages for mode-locked operation of lasers
166 such as a broad gain spectrum, a low linewidth enhancement factor, and ultrafast dynamics with low
167 saturation energies. A second crucial step is the implementation of tapered mode-locked lasers, which
168 consist of three segments: a saturable absorber to enable mode-locked operation, a ridge waveguide and a
169 taper with an opening angle of a few degrees. In gain guided tapered lasers, the mode defined by the ridge
170 waveguide is allowed to diffract into the taper without any lateral index discontinuities, under an angle
171 (typically a few degrees) defined by the mode profile of the ridge. The width of the taper at the facet is an
172 order of magnitude larger than that of a standard ridge waveguide, leading to a reduction of the power
173 density and therefore the facet load. In comparison to simple broad area lasers, which can provide only a
174 moderate beam quality, tapered lasers offer a very reasonable beam quality with beam parameter products
175 (M^2) below 2. This allows tight focusing of the output beam from a tapered laser. In addition to the
176 advantages for mode locked operation, quantum dot active layers have also benefits for tapered lasers, in
177 particular the small linewidth enhancement factor, which reduces beam filamentation in the taper and
178 therefore increases the beam quality of the output.

179 In order to test this, we utilized an MBE-grown laser structure based on AlGaInAs quantum dot
180 laser material, emitting at ~ 920 nm. The QDs were embedded in a 250 nm thick AlGaAs graded index
181 heterostructure (GRINSCH), and a symmetric AlGaAs cladding (see Table 2). The waveguide structures
182 were defined by electron-beam lithography and reactive ion etching, yielding devices with an overall
183 length of 2.250 mm and an absorber length ranging from 50 to 400 μm . In order to observe the transition
184 from normal to mode-locked operation, the output of the laser was analyzed using a fast fiber-coupled
185 optical receiver and a microwave spectrum analyzer. A significant narrowing of the RF-spectra was
186 observed when reverse bias was applied to the absorber segment, indicating the onset of mode-locking.
187 The peak of the RF frequency (see Fig. 4) is located at 18.05 GHz, corresponding to a cavity round trip
188 time of 55.4 ps.



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Table 2. Epitaxial layer structure of the QD based wafer.

Layer Type	Materials	THKNS μm	Dopant
Top Cladding			Beryllium
CAP layer	GaAs	0.25	
p-cladding	Al _{0.40} Ga _{0.60} As	1.5	
Active Medium			none
GRINSH	GaAs/AlGaAs SSL, Al _{0.18} Ga _{0.82} As	0.25	-
Barrier	GaAs	0.003	-
SK QD 4.9ML	Al _{0.15} Ga _{0.23} In _{0.62} As	-	-
Barrier	GaAs	0.003	-
GRINSH	GaAs/AlGaAs SSL, Al _{0.18} Ga _{0.82} As	0.25	-
Bottom Cladding			Silicon
n-cladding	Al _{0.40} Ga _{0.60} As	1.5	
Substrate	GaAs	-	Silicon

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193 Implementing a mode-locked miniaturized laser is the first step in creating a portable PU setup. Another
 194 quite massive element in standard PU setups is the delay line. The best solution there will be using
 195 Asynchronous Optical Sampling (ASOPS) [20], which requires two mode-locked semiconductor lasers.
 196 For this the jitter of the pulses defined by the noise in the laser becomes extremely important. Nowadays
 197 the jitter in monolithic semiconductor mode-locked lasers is below 100fs and by using external feedback
 198 it may be as small as 23fs [22] which does not reduce the temporal resolution for 1 ps long laser pulses.

199 This will pave the way for realizing portable sub-THz acoustic equipment for in-situ picosecond
 200 ultrasonic studies.

201 In conclusion, we have demonstrated picosecond ultrasonic setup on the basis of miniaturized
 202 mode-locked semiconductor laser. The measurement of a picosecond acoustic echo in Al film shows that
 203 the ultrasonic signal has the same shape and signal to noise ratio as in conventional setups with bulky

204 mode-locked lasers. The experiments show the prospective of designing and developing portable
205 picosecond ultrasonic setups integrated on a chip for utilization in medicine, biology and geology.

206 **CRedit authorship contribution statement**

207 **Michal Kobecki, Alexey V. Scherbakov, Thomas Czerniuk:** Picosecond ultrasonic setup and
208 measurements, preparing manuscript. **Giuseppe Tandoi, Eugenio Di Gaetano, Marc Sorel:**
209 Fabrication of MOCVD lasers; editing manuscript. **Christian Schneider, Martin Kamp, Sven**
210 **Höfling:** Fabrication of MBE lasers; editing manuscript. **Andrey V. Akimov,** Conceptualization,
211 first draft of the manuscript. **Manfred Bayer:** Supervision, conceptualization, editing the
212 manuscript

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